

**METHODS AND COMPOSITIONS FOR ETCH CLEANING
MICROELECTRONIC SUBSTRATES IN CARBON DIOXIDE**

Abstract of the Disclosure

A method of cleaning a microelectronic substrate is carried out by providing a cleaning fluid, the cleaning fluid comprising an adduct of hydrogen fluoride with a Lewis base in a carbon dioxide solvent; and then cleaning the substrate by contacting the substrate to the cleaning fluid for a time sufficient to clean the substrate.